TAKAFUJI et al. Appl. No. 10/802,735 Response to Office Action dated December 15, 2004

AMENDMENTS TO THE SPECIFICATION

Please replace the paragraph beginning on page 21, line 13 with the following amended paragraph:

The gate electrodes 133 are in this case made of a heavily-doped polycrystalline silicon film and W silicide. However, the gate electrodes 133 may be made solely sorely of polycrystalline silicon or made of other high melting point metals and silicide. The material of the gate electrodes 133 is determined in consideration of electric resistance and heat resistance.